

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	82	((pattern\$3 or etch\$3) same silicon) same ((first near mask\$3) same (chromium or "Cr"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/21 06:19
L2	58	1 and @pd<"20040120"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/21 06:21
L3	9	2 and ((second near mask\$3) same photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/21 06:21
S1	132	((pattern\$3 or etch\$3) same silicon) same mask\$3 and 216/47. ccls.	US-PGPUB; USPAT	OR	OFF	2005/09/21 06:15
S2	10	S1 and ((first near (mask\$3 or shield\$3)) same (metal or chromium or "Cr"))	US-PGPUB; USPAT	OR	OFF	2005/09/20 11:27